

PAT-NO: JP411172460A  
DOCUMENT-IDENTIFIER: JP 11172460 A  
TITLE: FORMATION OF FILM AND APPARATUS THEREFOR  
PUBN-DATE: June 29, 1999

**INVENTOR-INFORMATION:**

NAME COUNTRY  
MIYAGAWA, TAKUYA N/A

**ASSIGNEE-INFORMATION:**

NAME COUNTRY  
SEIKO EPSON CORP N/A

APPL-NO: JP09341620  
APPL-DATE: December 11, 1997

INT-CL C23C026/00 , B05D001/18 , C23C016/50 , B05D007/24 ,  
(IPC): C08F002/00

**ABSTRACT:**

PROBLEM TO BE SOLVED: To make it possible to easily form films on plastics or the like as well.

SOLUTION: A process chamber 64 is provided with a temp. controller 68 such that plural substrates 62 arranged in the process chamber 64 may be held at arbitrary temp. In addition, the process chamber 64 is so constituted that a carrier gas 88 past a monomer 82 and a reactive gas 70, such as gaseous fluorine or ozone, may be supplied via a raw material supply pipeline 90 and a reactive gas supply pipe 72 into the process chamber 64. The carrier gas 88 is held at the temp. higher than the temp. of the substrates 62 and the monomer 82 in the gaseous form included in the carrier gas 88 condenses and adheres to the surfaces of the substrates 62. When the substrates 62 are heated to

COPYRIGHT: (C)1999,JPO